

### Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (currently amended) A chemical vapor deposition apparatus comprising:  
a chamber having an inner space;  
~~a gas feed member for supplying a gas into the chamber;~~  
a susceptor disposed in the chamber and supporting a substrate;  
a diffuser partitioning the inner space of the chamber into first and second partitions  
and having an extension extended out from a boundary ~~a plurality of holes connecting the first partition and the second partition for gas communication;~~ and  
an insulating frame disposed between the chamber and the diffuser, said insulating frame being disposed on the extension of the diffuser, ~~wherein the diffuser includes an extension overlapping a surface of the insulating frame.~~
2. (original) The apparatus of claim 1, wherein the extension of the diffuser has an "L" shape.
3. (original) The apparatus of claim 1, wherein the diffuser comprises Al or stainless steel.
4. (original) The apparatus of claim 1, wherein the insulating frame comprises ceramic.
5. (original) The apparatus of claim 1, wherein the substrate comprises glass.
6. (original) The apparatus of claim 1, wherein the substrate is prepared for a liquid crystal display.
7. (original) The apparatus of claim 1, further comprising a blocking member for mixing and spreading the gas from the gas feed member before the gas passes through the holes of the diffuser.

8. (original) The apparatus of claim 1, wherein the diffuser is electrically powered and the susceptor is electrically grounded.

9. (currently amended) The apparatus of claim 1, further A chemical vapor deposition apparatus comprising:

~~a chamber having an inner space;~~  
~~a gas feed member for supplying a gas into the chamber;~~  
~~a susceptor disposed in the chamber and supporting a substrate;~~  
~~a diffuser partitioning the inner space of the chamber into first and second partitions and having a plurality of holes connecting the first partition and the second partition for gas communication;~~  
~~a diffuser frame incorporated into the diffuser; and~~  
~~an insulating frame disposed between the chamber and the diffuser.~~

10. (new) The apparatus of claim 1, wherein the extension overlaps a surface of the insulating frame facing the susceptor.

11. (new) A chemical vapor deposition apparatus comprising:  
a chamber having an inner space;  
a susceptor disposed in the chamber and supporting a substrate;  
a diffuser partitioning the inner space of the chamber into first and second partitions and having an extension of an "L" shape extended out from a boundary; and  
an insulating frame disposed between the chamber and the diffuser and disposed on the extension of the diffuser.

12. (new) The apparatus of claim 11, wherein the extension overlaps a surface of the insulating frame facing the susceptor.